



## Chapter 7.1

### ***Plasma Etch Training Class***

***(etchclass)***

#### **1.0 Class Purpose**

**1.1** This class will prepare you to use dry-etching (plasma) systems to etch your films.

#### **2.0 This Class is a Prerequisite for the Following Tools:**

**2.1** centura-3-5

**2.2** centura-met

**2.3** centura-mxp

**2.4** ionmill6

**2.5** lam6

**2.6** lam7

**2.7** lam8

**2.8** matrix-etch

**2.9** oxford-icp

**2.10** oxford-rie

**2.11** primaxx

**2.12** semi

**2.13** sts2

**2.14** sts-oxide

**2.15** technics-c

**2.16** xetch

**2.17** yes-g500

**2.18** Always refer to the Prerequisite section in MercuryWeb for the most up-to-date list of prerequisites for any piece of equipment.

#### **3.0 Training Procedure**

**3.1** This class provides background information for a set of tools.

**3.2** Prerequisites for this class are: vacuumclass

**3.3** Timeline:

**3.3.1** Watch the videos (see Section 5.0).

**3.3.2** Take the online exam. You may take the exam from anywhere (not just the office).

**3.4** After passing the online exam, you will be automatically qualified on this class.

**4.0** **Reference Slides & Applicable Documents**

**4.1** [Reference Slides Used in the Video](#)

**5.0** **Videos**[Etch Training Workshop Video Course Part 1.mp4](#)

**5.1** Watch the following videos to get trained on this class. The videos should be watched in order. Be sure to read appendix A - Policy Addendum as well.

**5.2** [Video 1 - Plasma Etch Introduction](#)

**5.3** [Video 2 - Reaction Chemistry](#)

**5.4** [Video 3 - Choosing a Tool](#)

**5.5** [Video 4 - Substrate Behavior](#)

**6.0** **Appendix A - Policy Addendum for NanoLab Policies not yet covered in video format**

**6.1** All photoresist masks must be hard baked before entering a plasma etch tool in the NanoLab.